







Attorney Docket: 2022/48819

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Bulent M. Basol et al.

Serial No.: 09/671,800

Group Art Unit: 1741

Filed: September 28, 2000

Examiner: W. Leader

Title:

PROCESS TO MINIMIZE AND/OR ELIMINATE CONDUCTIVE MATERIAL

COATING OVER THE TOP SURFACE OF A PATTERNED SUBSTRATE AND

LAYER STRUCTURE MADE THEREBY

ADDITIONAL CLAIMS FEE CHART

Commissioner for Patents 20231 Washington, D.C.

Transmitted herewith is a Supplemental Reply for filing and the filing fee is calculated below:

For_		No. After Amendment		Highest No. Prev. Filed		No. Extra		Rate Fee	
Total C Indep. Multipl	Claims	91 14 dent	- - Claim	88 14 Presented	=	3	x x	\$ 9/\$18 \$40/\$80 \$135/\$27	= \$ 0
								TOTAL:	\$54

A check in the amount of \$54.00 is enclosed. XX

The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment, to Account XXNo. 05-1323 (Docket #2022/48819). A duplicate copy of this sheet is attached.

November 13, 2002

Richard R. Diefendorf Registration No. 32,390

CROWELL & MORING LLP

P.O. Box 14300

20044-4300 Washington, D.C. Telephone No.: (202) 624-2500

(202) 628-8844 Facsimile No.:

RRD:msy

TC 1700 MAIL ROOM



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THEREBY

SUPPLEMENTAL REPLY

Commissioner for Patents Washington, D.C. 20231

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NOV 15 2002

Supplemental to the Reply filed November 12, 2002, electing the invention defined by claims 17-22, 58-60, 66, and 73-76 (invention II) for examination, kindly amend the claims of this application as follows.

Please cancel claims 20 and 60.

Please amend claims 17-19, 21, 58 and 59 as follows. A marked-up version of the amended claims is included at the End of this document.

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17. (Amended) A layer structure usable in manufacturing an integrated circuit made by a process comprising:

providing a patterned substrate,

supplying an electrolyte solution out of which a conductive material can be plated, under an applied potential, over/a surface of said patterned substrate,